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Supplementary Information

Metal Oxide-Free Flexible Organic Solar Cells with 0.1 M Perchloric Acid Sprayed Polymeric Anodes

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Fig. S1 Aggregate morphology of the PEDOT:PSS anodes with >99.5 wt% CH_3SO_3H soaking treatment.



Fig. S2 Molecular structures of PEDOT:PSS, PDINO and PDINN.



Fig. S3 Plotted PCE values of single-junction flexible OSCs reported in literatures and in this work.



Fig. S4 The integrated current density of the flexible OSCs based on the PEDOT:PSS electrodes with the $HClO_4$ treatments.



Fig. S5 V_{oc} versus light intensity of the flexible OSCs based on the PEDOT:PSS electrodes with the HClO₄ treatments (n=1.45) and the CH₃SO₃H treatments (n=1.58), respectively.



Fig. S6 The dark current density of the flexible OSCs based on the PEDOT:PSS electrodes with the $HClO_4$ treatments (a) and the CH_3SO_3H treatments (b).

Tab. S1 Summaries of photovoltaic characteristics of single-junction flexible organicsolar cells with flexible transparent electrodes

Flexible electrode	Preparation method	Active layer	PCE (%)	Refer.

ZnO/Cu(8.0 nm) on Cu(O)/ZnO	Magnetron sputtering/Thermal evaporation	PTB7:PC71BM	6.70	S1
ZnO/Cu(9.5 nm) on Cu(O)/ZnO		PTB7:PC ₇₁ BM	7.7	S2
ZnO/Cu (0:5%)(7 nm)/ZnO		PTB7-Th:PC71BM	7.65	S3
TiO ₂ /ZnO/Ag(8.0 nm)/ZnO	Vacuum sputtering	PBDB-T:IT-M:PC ₇₁ BM	10.48%	S 4
			Best: 10.62	
Ag grid/PEDOT:PSS	Thermal evaporation/Solution preparation	PTB7-Th:PC71BM	6.58	S5
Ag mesh/PEDOT:PSS	Printing/Solution preparation	PTB7:PC ₇₁ BM	6.73	S6
Ag NW	Solution preparation	PTB7-Th:PC ₇₁ BM	8.75	S7
Ag island/PEDOT:PSS	Thermal evaporation/Solution preparation	PTB7-Th:PC ₇₁ BM	9.8	S 8
			Best: 9.9	
Ag NW/Al-ZnO	Solution preparation	PM6:IT-4F	12.02	S9
Ag/Cu grid	Nanoimprinting and electrodeposition	NF3000-P:NF3000-N	12.26	S10
Ag NW/PSSNa	Solution preparation		13.1	\$11
Ag NW/Al-ZnO	Solution preparation	PBDB-T-2F:Y6	14.93	\$12
			Best:15.21	
Transferred Ag NW/ZnO	Solution preparation	PM6:N3:PC71BM	15.6	S13
			Best: 16.1	
Graphene	Chemical vapor deposition	РМ6:Ү6	14.8	S14
			Best: 15.2	
PEDOT:PSS	Aqueous solution preparation	PBDTT-S-TT:PC71BMP	6.42	S15

PEDOT:PSS	Aqueous solution preparation	TB7-Th:PC ₇₁ BM	7.7	S16
PEDOT:PSS	Aqueous solution preparation	PBDB-T:IT-M	10.03	S17
			Best: 10.12	
PEDOT:PSS	Aqueous solution preparation	PCE-10:IEICO-4F	12.5	S18
PEDOT:PSS	Aqueous solution preparation	PM6:Y6:PC ₇₁ BM	14.06	S19
PEDOT:PSS	Aqueous solution preparation	PM6:Y6	16.44	Here

Best:16.71

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Tab. S2 Physical Properties of PEDOT:PSS (Clevios PH1000) and PEDOT:PSS (Clevios P VP AI4083) Used to make transparent electrodes and hole transport layers, respectively

Product	Solids	PEDOT:PSS ratio	Particle size	Viscousity	Film	Work
	content	(by weight)	(nm)	(cP)	resistance	function
			d50		(Ω.cm)	
P VP	1.3–1.7%	1:6	Max:35	5–12	500–5000	5.0–5.2
AI4083			distribution50			
PH1000	1.0–1.3%	1:1.25	Major:120	15–50	<0.0012	4.8–5.2 eV
					(with doping)	